by S. Camillo

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> d his full

     (FILE 'HOME' ENTERED AT 10:00:20 ON 01 NOV 2001)

     FILE 'USPATFULL' ENTERED AT 10:01:28 ON 01 NOV 2001
               SET ABBREV ON
               SET PLURAL ON
L1        102288 SEA ABB=ON  PLU=ON  (REMOV? OR ELIMINAT? OR DISSOLV? OR
               DISSOLUT? OR STRIP? OR ETCH?) (10A) (ORGANIC?)
L2        402041 SEA ABB=ON  PLU=ON  (ACETIC? OR "CH3COOH" OR "CH.SUB.3COOH"
OR
               ACETATE? OR CARBONATE?)
L3         22378 SEA ABB=ON  PLU=ON  L1 (P) L2
L4            55 SEA ABB=ON  PLU=ON  L3 (P) (WAFER OR SEMICONDUCTOR? )
               D L4, 1-55, TI
               D L4, 1, 53, BIB, AB, KWIC
L5         16302 SEA ABB=ON  PLU=ON  (ACETIC? OR "CH3COOH" OR "CH.SUB.3COOH"
OR
               ACETATE? ) (P) (SCAVENGER? OR ADDITIVE?)
L6          3160 SEA ABB=ON  PLU=ON  L5 AND L1
L7           301 SEA ABB=ON  PLU=ON  L5 (P) L1
L8            31 SEA ABB=ON  PLU=ON  L7 AND (WAFER? OR SEMICONDUCTOR?)
               D L8, 1-31, TI
               D L8, 5, BIB, AB, KWIC
L9         30846 SEA ABB=ON  PLU=ON  (ACETIC? OR "CH3COOH" OR "CH.SUB.3COOH"
OR
               ACETATE? OR BICARBONATE? OR CARBONATE) (P) (SCAVENGER? OR
               ADDITIVE?)
L10          391 SEA ABB=ON  PLU=ON  L9 (P) L1
L11           43 SEA ABB=ON  PLU=ON  L10 AND (WAFER? OR SEMICONDUCTOR?)
               D L11, 1-43, TI
               D L11, 6, BIB, AB, KWIC
L12        23734 SEA ABB=ON  PLU=ON  (ACETIC? OR "CH3COOH" OR "CH.SUB.3COOH"
OR
               ACETATE? OR BICARBONATE? OR CARBONATE) (P) L1
L13         1190 SEA ABB=ON  PLU=ON  L12 AND (SCAVENGER?)
L14           93 SEA ABB=ON  PLU=ON  L13 AND (WAFER? OR SEMICONDUCTOR?)
               D L14, 1-93, TI
L15        30846 SEA ABB=ON  PLU=ON  (ACETIC? OR "CH3COOH" OR "CH.SUB.3COOH"
OR
               ACETATE? OR BICARBONATE? OR CARBONATE) (P) (SCAVENGER? OR
               ADDITIVE?)
L16           80 SEA ABB=ON  PLU=ON  L15 (P) (WAFER? OR SEMICONDUCTOR?)
L17           29 SEA ABB=ON  PLU=ON  L16 AND L1
               D L17, 1-29, TI
               D L17, 11, BIB, AB, KWIC
L18         1074 SEA ABB=ON  PLU=ON  (ACETIC? OR "CH3COOH" OR "CH.SUB.3COOH"
OR
               ACETATE? OR BICARBONATE? OR CARBONATE) (10A) (SCAVENGER?)
L19          181 SEA ABB=ON  PLU=ON  L18 AND (SEMICONDUCTOR? OR WAFER?)
L20            6 SEA ABB=ON  PLU=ON  L18 (P)(SEMICONDUCTOR? OR WAFER?)
               D L20, 1-6, TI
               D L20, 5, KWIC
L21          260 SEA ABB=ON  PLU=ON  (ACETIC? OR "CH3COOH" OR "CH.SUB.3COOH"
OR
               ACETATE?) (10A) (SCAVENGER?)
L22           23 SEA ABB=ON  PLU=ON  L21 AND (SEMICONDUCTOR? OR WAFER?)
               D L22, 1-23, TI
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                D L22,8  TI
                D L22    KWIC
L23          1481 SEA    ON  PLU=ON  (ACETIC? OR "CH3C    OR "CH.SUB.3COOH"
OR
                ACETATE?) (P) (SCAVENGER?)
L24           398 SEA ABB=ON  PLU=ON  L23 AND L1
L25            39 SEA ABB=ON  PLU=ON  L23 (P) L1
                D L25, 1-39, TI
                D L25, 18, BIB, AB, KWIC
                D L24, 1-398, TI
L26           196 SEA ABB=ON  PLU=ON  L1 (P) (SCAVENGER?)
L27            10 SEA ABB=ON  PLU=ON  L26 AND (SEMICONDUCTOR? OR WAFER?)
                D L27, 1-10, TI
                D L27, 9, BIB, AB, KWIC
L28        326119 SEA ABB=ON  PLU=ON  (ACETIC? OR "CH3COOH" OR "CH.SUB.3COOH"
OR
                ACETATE?)
L29           143 SEA ABB=ON  PLU=ON  L26 AND L28
L30            39 SEA ABB=ON  PLU=ON  L26 (P) L28
                D L30, 1-39, TI
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13651 USPATFULL
TI Polymeric etch resist strippers and method of using same
IN Schevey, William R., Hawley, PA, United States
Kremers, Frank J., Jordan, NY, United States
PA Allied Chemical Corporation, New York, NY, United States (U.S. corporation)
PI US 3871929 19750318
AI US 1974-438127 19740130 (5)
DT Utility
FS Granted
EXNAM Primary Examiner: Powell, William A.
LREP Friedenson, Jay P., Dunn, Michael L.
CLMN Number of Claims: 17
ECL Exemplary Claim: 1
DRWN No Drawings
LN.CNT 223
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB **Strippers** for **removal** of **organic** films and deposits, such as polymeric **etch** resists employed in the manufacture of **semiconductors** and microcircuits, comprising a surface active agent, phenol or **acetic** acid, phenol sulfonic acid and chlorinated hydrocarbon.
AB **Strippers** for **removal** of **organic** films and deposits, such as polymeric **etch** resists employed in the manufacture of **semiconductors** and microcircuits, comprising a surface active agent, phenol or **acetic** acid, phenol sulfonic acid and chlorinated hydrocarbon.
SUMM A class of compositions useful for **removing organic** polymeric deposits from the surface of materials used in the manufacture of